SiW-ECAL Long Slab Test Bench Technical Document

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For long SiW-ECAL testing, a dedicated bench would allow to complete much more efficiently some measurements in controlled mechanical and electrical conditions. The main purpose is to test the response of ASU at the end of a SLAB, typically after a buffering of 5–6 ASU's, using an γ-ray radioactive source for effectiveness. A secondary purpose is to allow precision measurement with the source collimated.

This document summarizes all the technical details concerning the design and realisation of such a test bench. This device could also serve as a support for beam test operation (e.g. at PHIL).

1 Introduction

The SiW-ECAL Slabs are made of several ASU (Assembly Single Units) stitched together. The readout and cooling is performed at one end. All the signal and power must travel across all the ASU. The integrity of the signal and the stability of the LV supply has to be tested for up-to 7 and 10 ASU's (resp. in the barrel and EndCaps of ILD in option of the largest geometry).

For testing purpose a Functional Long Slab (FLS) is typically composed of a DIF, an Adaptor Board, an *equipped ASU*, several *naked PCB*'s and a final equipped ASU.

[DESSIN]

Equipped ASU could either be

- a PCB with glued Wafers (1 to 4) or
- a PCB with Wafers connected via a matrix of springs to a dispatch pannel

Naked PCB do not hold Wafers.

2 Purpose / needs

2.1 Test the powering and signal transmission in the SLAB

2.1.a Powering

The ASICs must be powered in pulsed mode, typically: up to 3-4 ms at 5 to 20 Hz. Several tensions should be brought to the ASIC with various stability required (see annexe). Check the stability of the line after *n* ASU.

2.1.b Signal transmission

Check clock distribution (eye diagram)

2.2 Test of response at the end of the SLAB

To test the response of an ASU at the end of the SLAB, a reproducible signal is needed:

- for naked PCB's: electric [possible if polarisation of the ASIC's ?]
	- a PCB could emulate a wafer
- for ASU: physical, either from laser, cosmics or X-rays.

For this a single aperture anywhere is sufficient: a reproducible signal injected at a given time or given rate [to be detailled wrt to expectation in PP mode…] in one or several cells is enough, to be compared between the close and far end of the slab.

2.3 Test of response of individual pixels at the centre of an ASU.

With a collimated source [X-rays or beam] fine scans could be performed across single pixels, pixel boundaries, guard rings, inter-wafer gap. This scans can be performed e.g. along the pixel axis (red, solid path in figure [1\)](#page-1-0), or along the diagonal (purple, dotted path).

Figure 1: Schematic layout of the wafers, guard rings & gaps (not to scale). The Bold lines indicate possible paths for fine scans.

The needed scan step is typically a fraction of the smallest structure. Typically Inter-wafers gaps are \sim 100 μm wide, guard rings \sim 300–500 μm, inter-cells gaps \sim 50 μm [A VERIFIER]. A step of 20-50 μm should suffice over a span of a couple of centimetres.

Figure 2: Expected response from the scans across 3 pixels and an inter-wafer gap

3 Implementation

3.1 Service and test trays

One *Service Tray* for the adaptor board + DIF board stitched to up-to 3 *Test Trays* having a capacity of 3 ASU's or PCB's each.

The trays have a hole or a thinner lower surface under the middle [end if they are reversible] [DESSIN IMPLEMENTATION DE MICHAEL]

Figure 3: Service Tray and two Test Tray.

blablabla

3.2 Moving arm

Precision, length needed from the mechanical point of view…

 x^{ξ}

3.3 DAQ

Rate limitation ? Conversion times ? \rightarrow max rates with PP

3.4 Sources

Five types of signals could be envisaged: cosmics, high energy beta or low energy gammas from a radio-active source, IR laser source, 3 MeV electron beam (PHIL).

The energy deposited in the depletion region, its shape (pic or spread) and the amount of material to to cross before deposition, as well as the rate of the signal, will determine the source.

3.4.a Cosmics

High energy muons from cosmics rays provide a minimum signal of:

mip_⊥ = 3.876 MeV cm⁻¹ × 0.0320 cm = 0.124 MeV = 124 keV

The distribution is $\propto \cos^2\theta$ with θ being the angle wrt the vertical.

The flux is \sim 1/dm²/s, so typically 1/400 Hz for 5×5mm² cells.

3.4.b Beta source

A source of ⁹⁰Sr-⁹⁰Y provides betas of up-to 546 keV and 2.2 MeV following a continuous spectrum. High energy electrons will traverse the 320 μm thick Silicon, but not always along a straight path. An initial energy of at least 250 keV is needed (see attached Annex)

A small (in dimension) 37 MBq ⁹⁰Sr source is available at LLR with a holder and a collimator, still usable for a couple or years. A new collimator would need to retrain the beam signal spread for the fine scan measurements.

An aperture of 50 μ m at 1 cm from the centre of the source would provide \sim 1.162 MHz of ß.

[WHICH FRACTION ABOVE 250 KEV ?]

3.4.c Gamma source

Gamma sources of low energy would provide a peaked signal that could be at the value of the expected mip response. Photons would traverse shielding and only a small fraction would interact in the Silicon wafers. One could place a source at \sim 1cm from the wafers behind an aluminium plate. At this distance, it would covers well ~8×8 cells (4 cm²) with $1/6th$ of the flux.

Baryum133 (¹³³Ba)

A source of ¹³³Ba would provide 81keV (34%) and 356keV (64%). It has a T_{γ} of 10 years.

The radiation length of 356 keV- γ in Silicon is 1/(1.009e-01 cm²/g * 2.33 g/cm³) = 4.25 cm. About 0.7% of the γ 's will interact in 320 µm of which only 4‰ in photoelectric.

The radiation length of 80 keV- γ in Silicon is 1/(6.469e+01 cm²/g * 2.33 g/cm³) = 66 μ m mostly in photoelectric.

Voir: http://space.unibe.ch/staff/wurz/7474/Course_6a.pdf]

Cobalt 57 (⁵⁷Co):

 $T\frac{1}{2} = 0.744$ years, EC

From Taikan's presentation: 122keV (86%), 136 keV (11%)

(adc_hq[2][0] - 311.298017)/100.582860 {trig_hq[2][0] == 1&&iscadif == 0}

Illustration 1: ⁵⁷Co spectrum in 300μm wafers (?) from Kyushu group (after pedestal & Gain calibration).

The radiation length of 122 keV- γ in Silicon is 1/(1.318E-02 cm²/g * 2.33 g/cm³) =32 cm mostly in photoelectric. 1% in 300μm Si.

3.4.d IR-Laser

3.4.e Pulsed electron beam (PHIL)

4 Planning

5 Resources

References:

- [1] [http://www3.nd.edu/~wzech/Application-Note-AN34-ExperimentsNuclear-Science-](http://www3.nd.edu/~wzech/Application-Note-AN34-Experiments-Nuclear-Science-Experiment-6.pdf)[Experiment-6.pdf:](http://www3.nd.edu/~wzech/Application-Note-AN34-Experiments-Nuclear-Science-Experiment-6.pdf) ORTEC manual for TP of electrons in Si: 133 Ba spectrum, etc
- [2] Physics for Radiation Protection: A Handbook by James E. Martin [{in google books}](file:///Users/boudry/ILC/ECAL/Org/Banc%20Test%20Slabs%20Longs/Physics%20for%20Radiation%20Protection:%20A%20Handbook%20Par%20James%20E.%20Martin)

Revisions

Annexes

5.1 Poweringof the Skiroc2

5.2 Stopping power of electron in Silicon

<head><title>NIST STAR Database</title><script language="JavaScript

